

Amendment to the Specification

Please replace the Abstract in page 25 with the following paragraph:

a' --The present invention relates to a ~~nevel~~ photoresist composition sensitive in the deep ultraviolet region and a method of processing the ~~nevel~~ photoresist, where ✓ the photoresist comprises a novel copolymer, a photoactive component, and a solvent. The novel copolymer comprises a unit derived from an ethylenically unsaturated compound containing at least one cyano functionality and a unit derived from an unsaturated cyclic non aromatic compound.--